



EU - SOUTH KOREA – Joint Researchers Forum
on Semiconductors



Silicon Carbide Electronics for Advanced Power, Sensing and System Integration

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 Brussels (Belgium)
March 25-26, 2024

EU – SOUTH KOREA - Joint Researchers Forum
on Semiconductors
Name



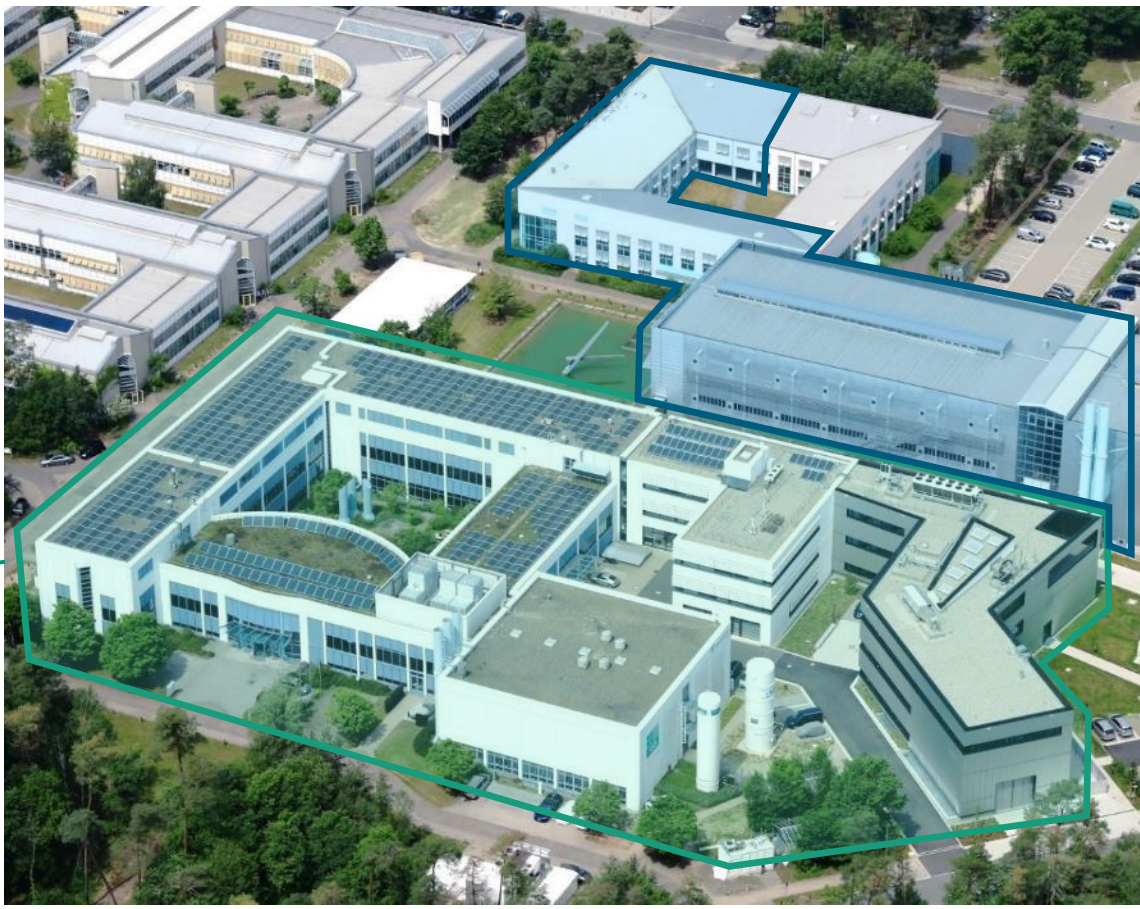
Introduction to IISB



Headquarters ●
Sub-offices ○



FAU Friedrich-Alexander-Universität
Erlangen-Nürnberg



Electron Devices
**Prof. Dr.-Ing. habil.
Jörg Schulze**
Director of IISB



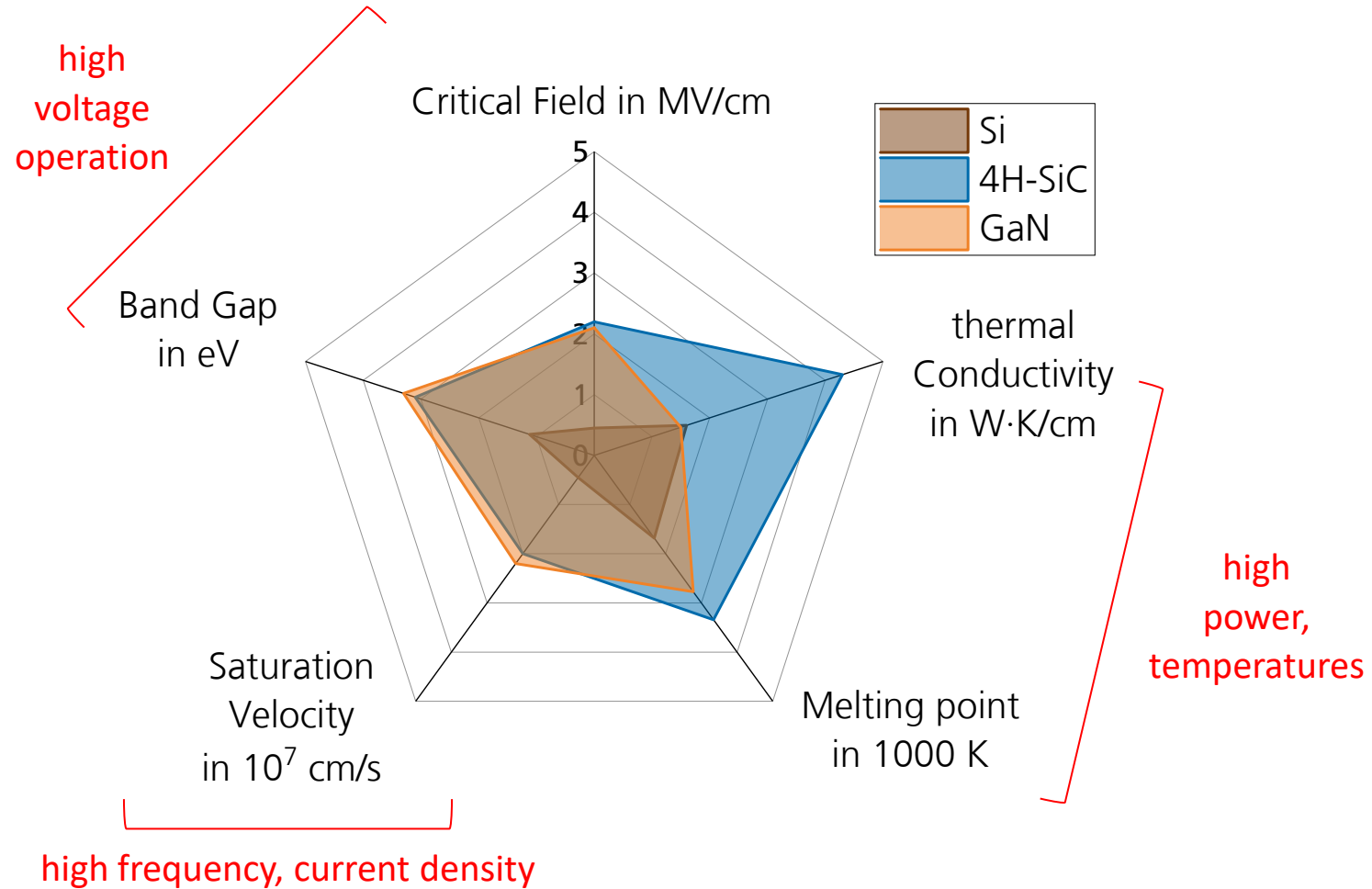
Power Electronics
**Prof. Dr.-Ing.
Martin März**

EU – SOUTH KOREA – Joint Researchers Forum on Semiconductors
Michael Jank, **Fraunhofer IISB**

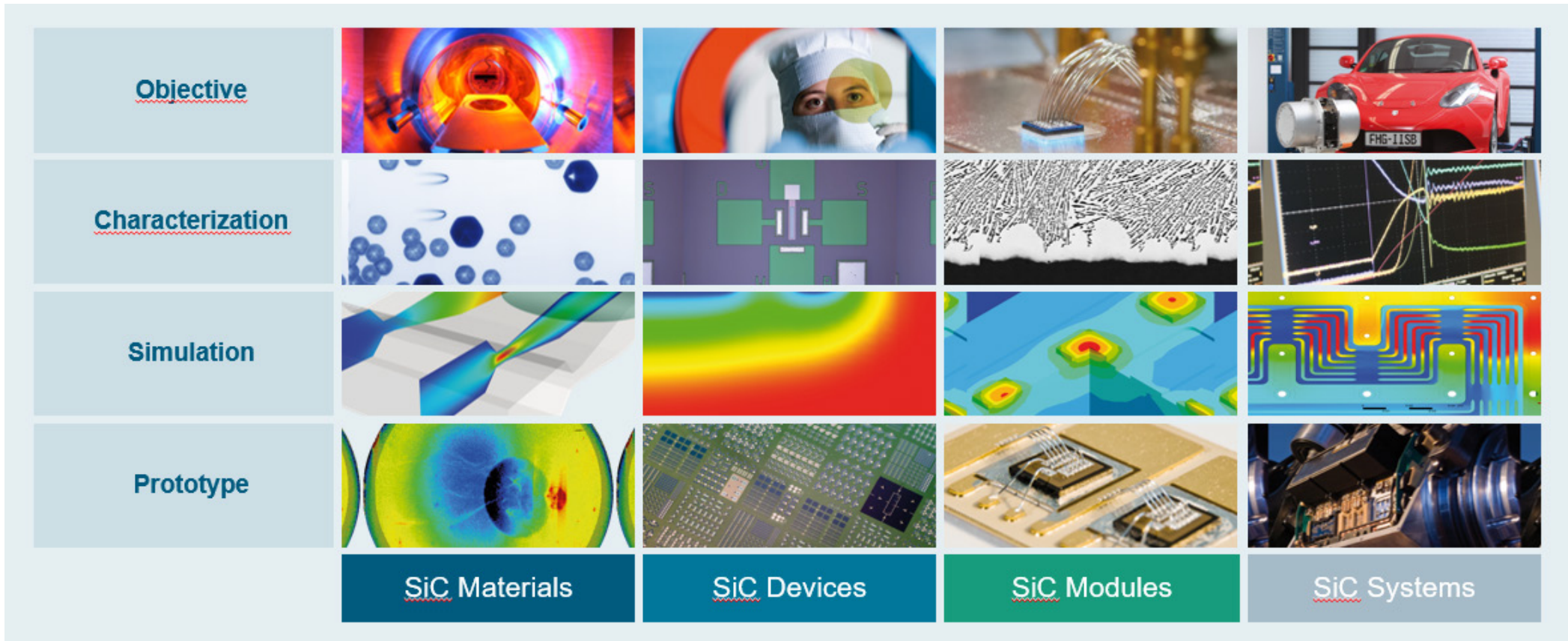


- Silicon Carbide Technologies at Fraunhofer IISB
- MOS and Bipolar SiC Power Devices
- High-Temperature SiC CMOS Technology

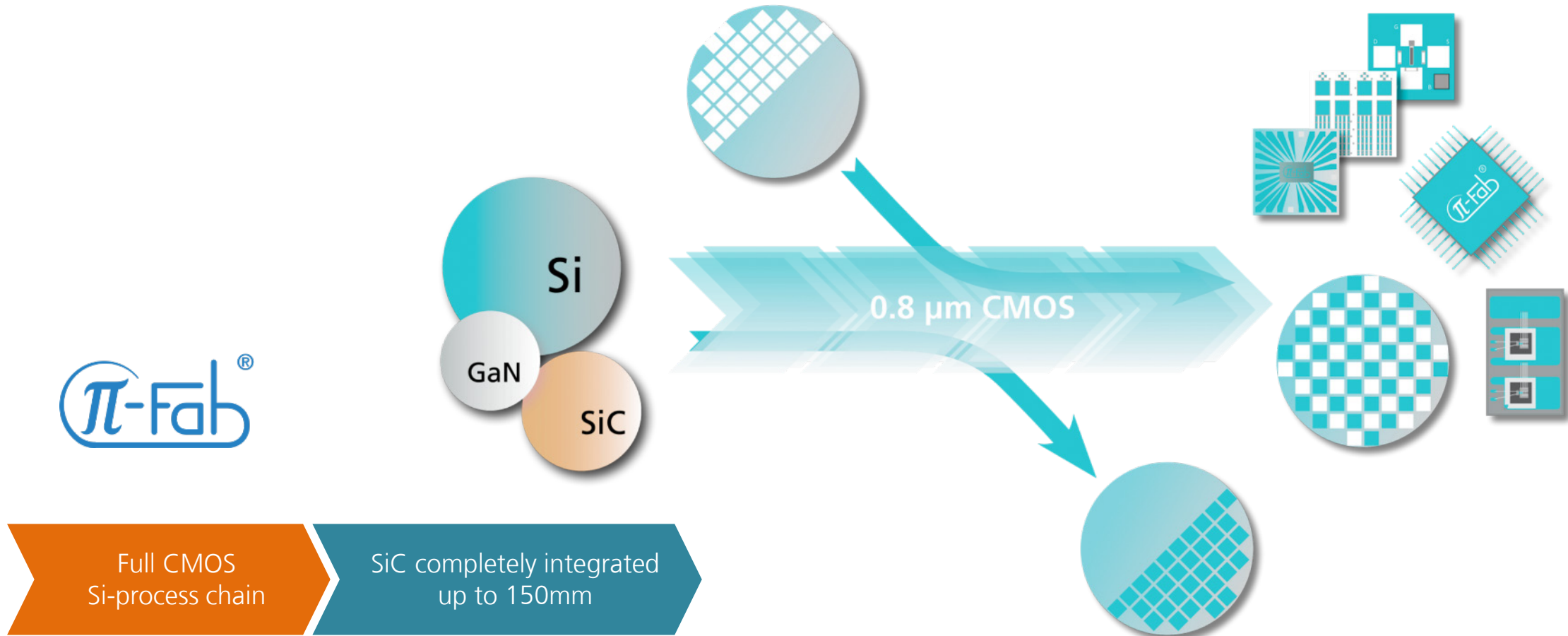
Materials Properties of SiC



- IISB's Integrated Vertical Value Chain



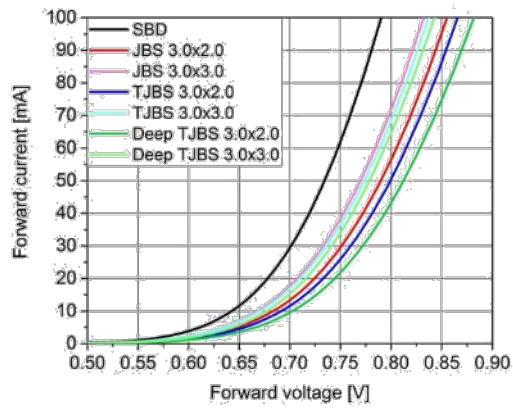
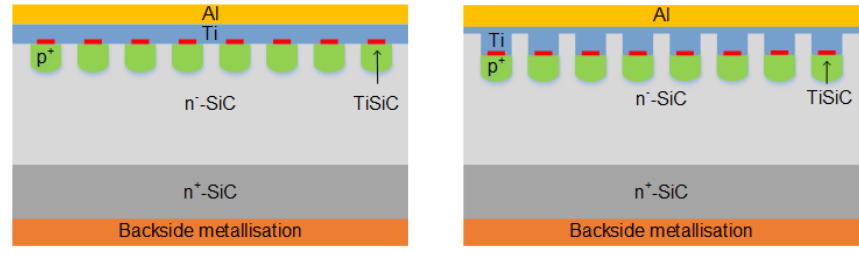
SiC Process Environment



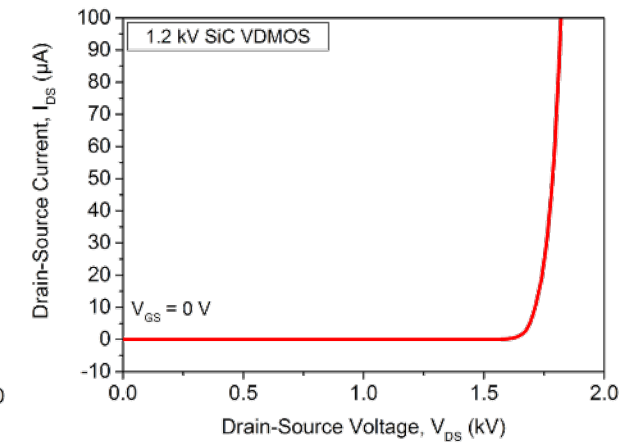
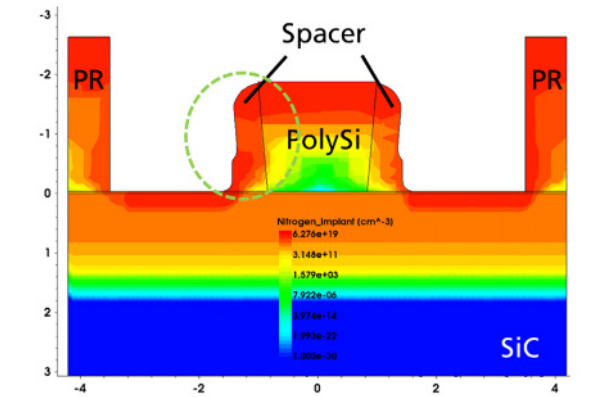
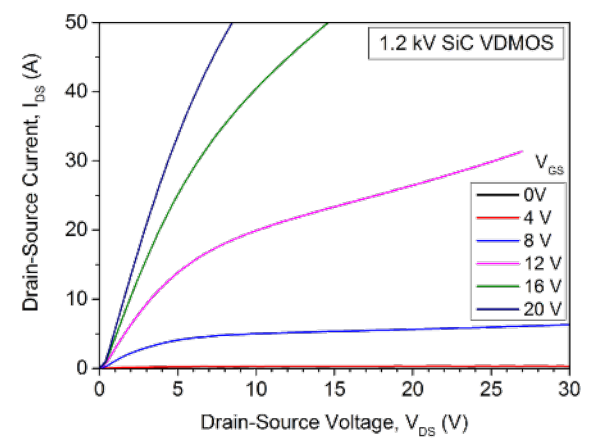
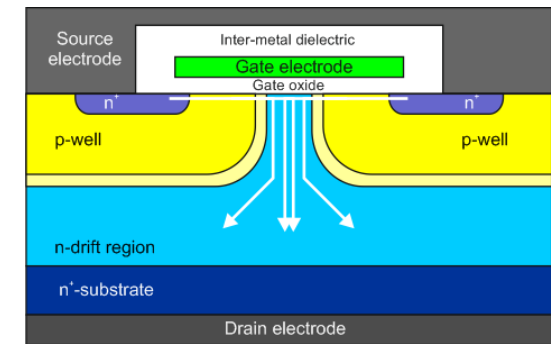
SiC Power Devices

- Bipolar and MOS Power Devices

Merged Schottky/pn Diodes

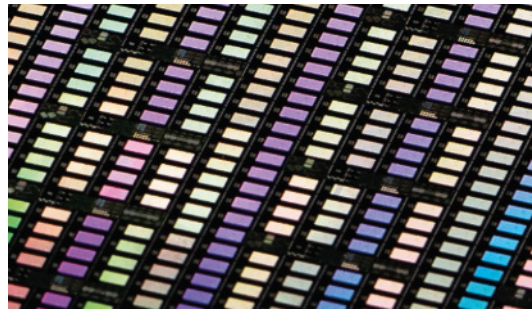


1.2 kV VDMOS (planar)

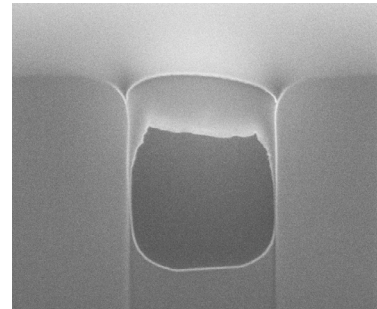


- Advanced Trench Technologies

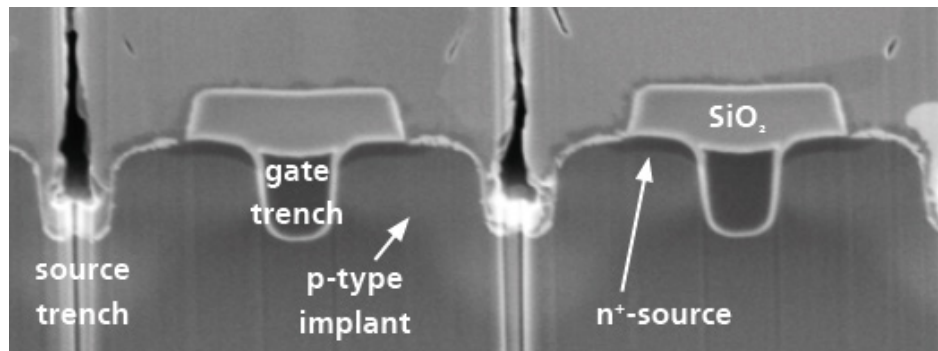
1.2 kV TrenchMOS



Devices on wafer



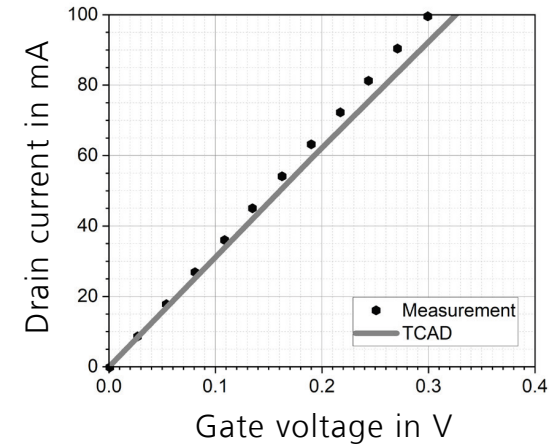
Poly-Si-plug with oxidation



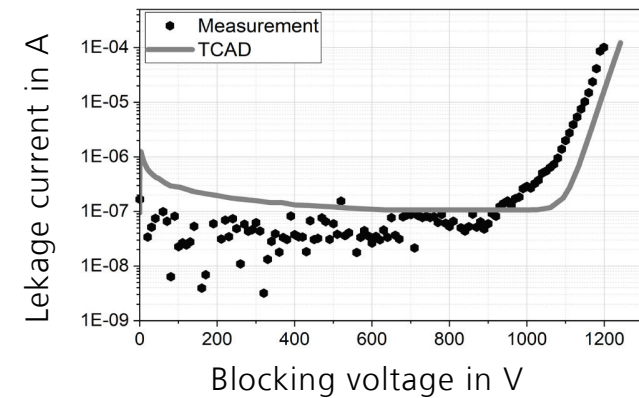
FIB cross-section of active area

Electrical Performance

Transfer characteristics (lin.)

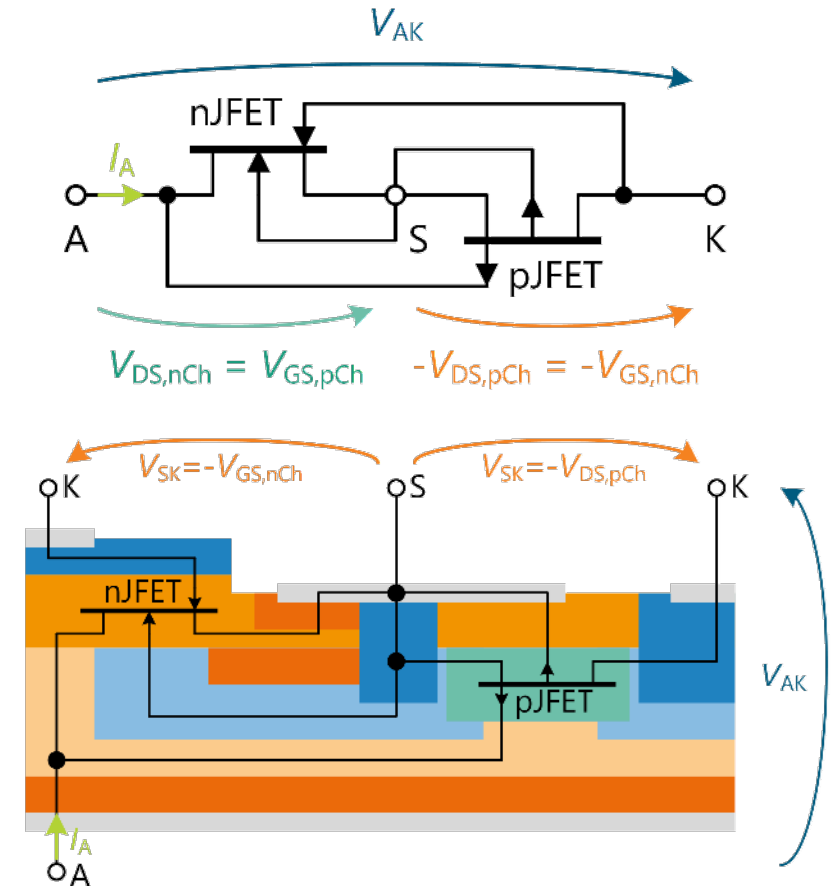
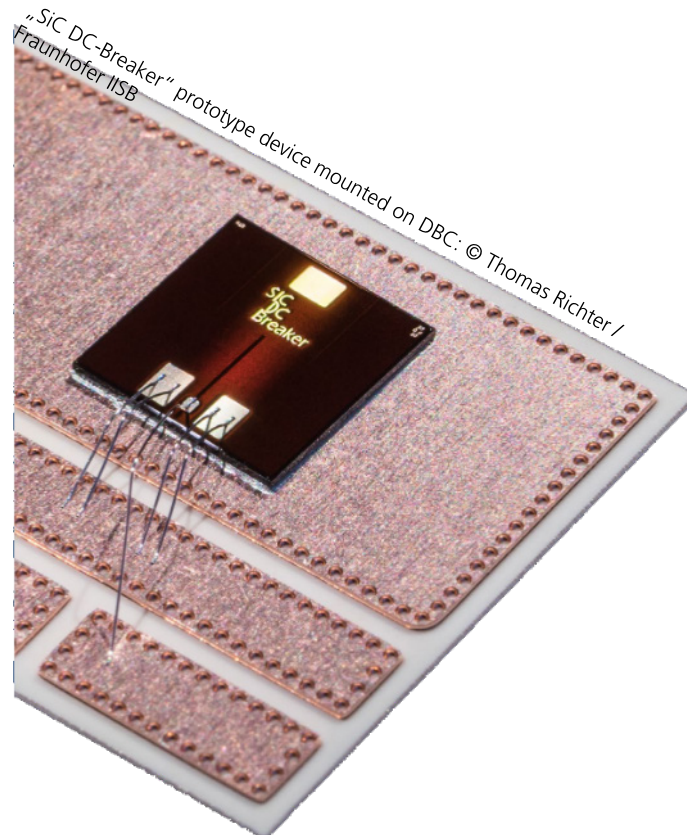


Reverse operation

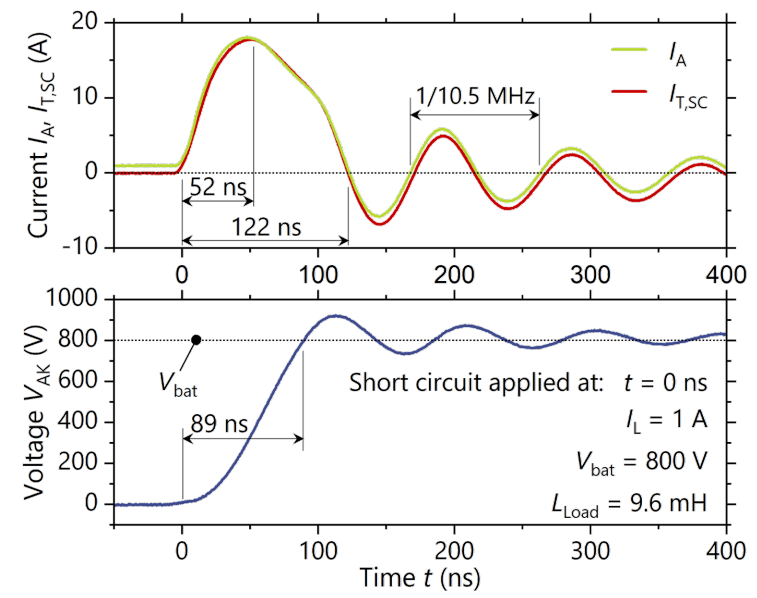
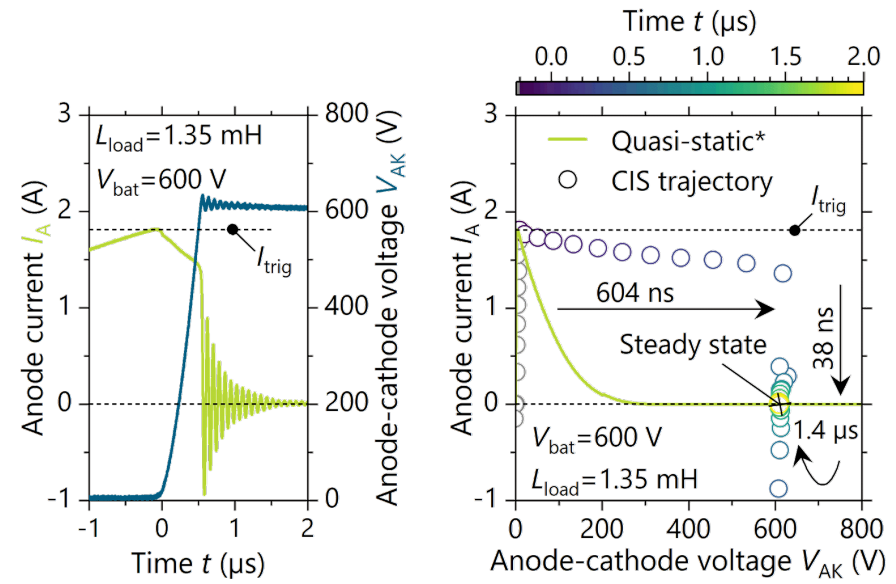
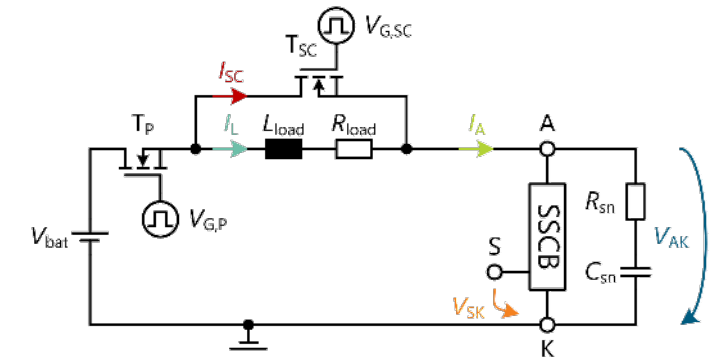


- Solid-State Circuit Breaker

- Self-Supplied
- Self-Sensed
- Self-Sustained



- Solid-State Circuit Breaker
 - Self-sensed sub- μ s switching



SiC CMOS Technology for harsh environments

- Operation > 500°C

Energy Industries	Geothermal	Oil & Gas Exploration	Industrial Gas Turbines	Aircraft Engines	Automotive Engines
Required Sensing Temperatures	375°C	275°C	600°C	600°C	300°C
Desired Sensing Measurands	<ul style="list-style-type: none"> • Pressure • Temperature • H₂S • Strain 	<ul style="list-style-type: none"> • Pressure • Temperature • Hydrocarbon • Strain 	<ul style="list-style-type: none"> • Pressure • Temperature • Flame speed • Acceleration 	<ul style="list-style-type: none"> • Pressure • Temperature • Flame speed • Acceleration 	<ul style="list-style-type: none"> • Pressure • Temperature • Flame speed • O₂

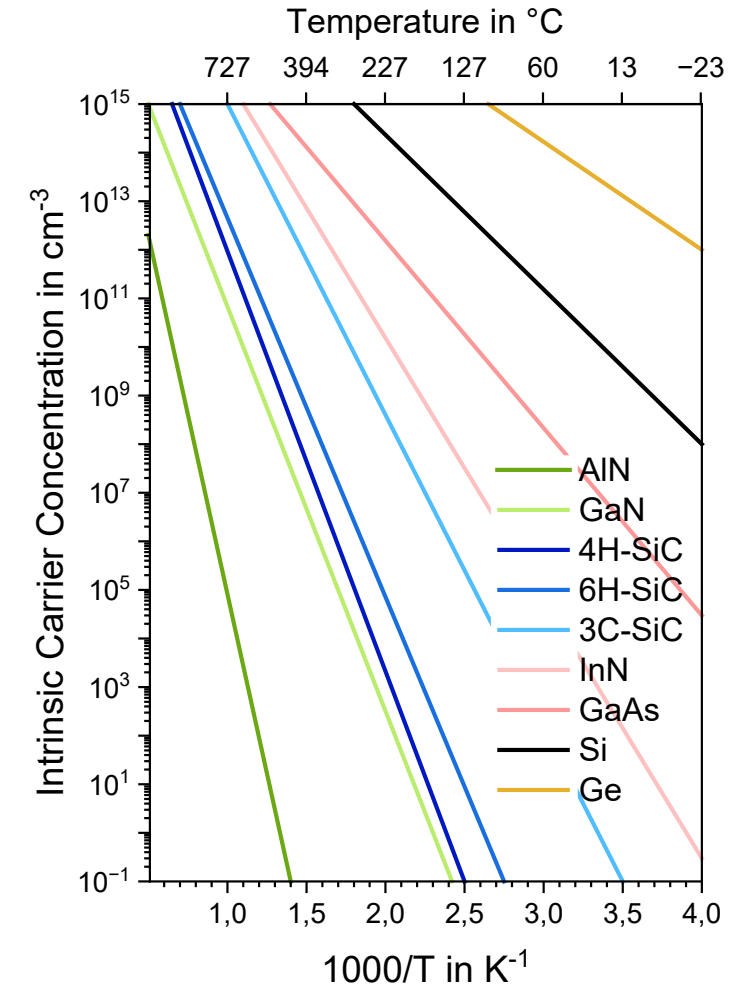
Harsh Environment Sensor Cluster, University of California, San Diego

Power Electronics

Integrated Gatedriver:

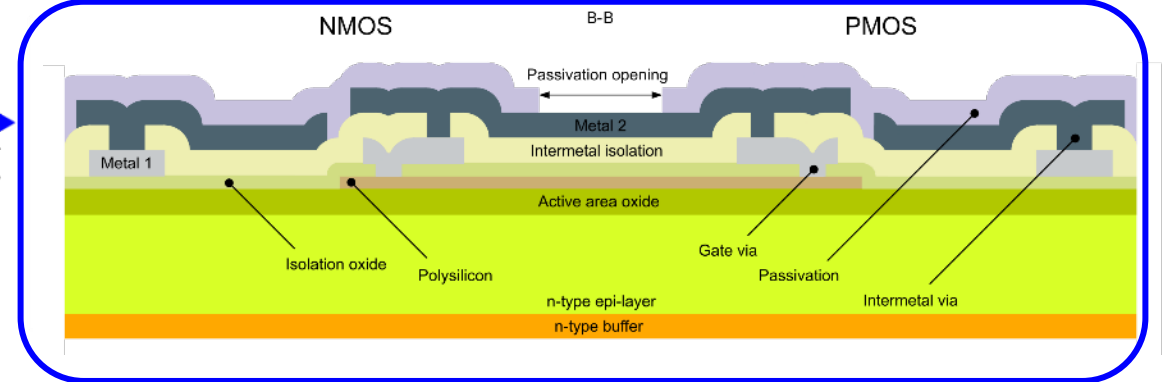
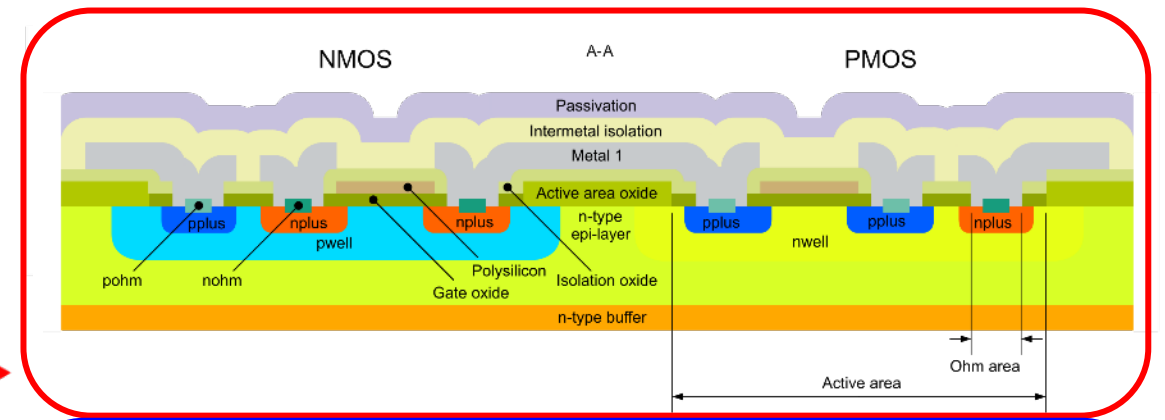
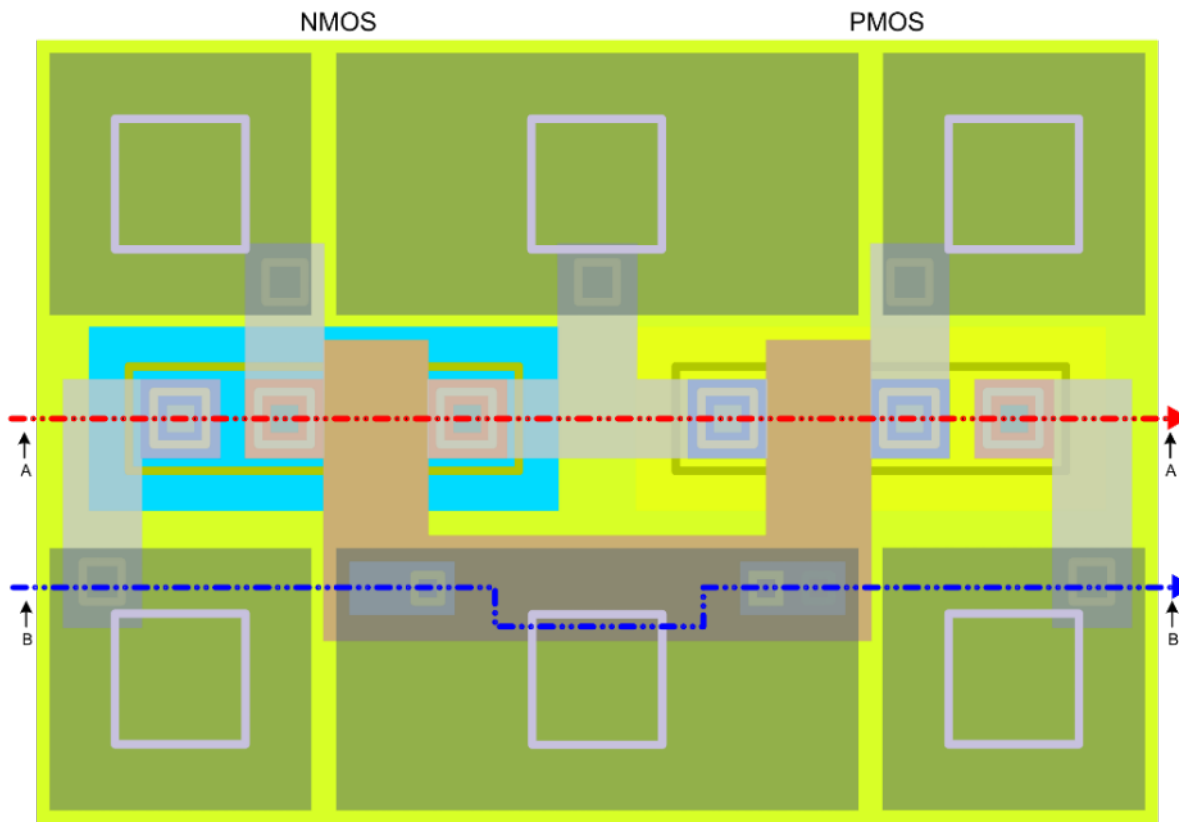
- Current
- Temperature

- High switching frequencies
- reliability



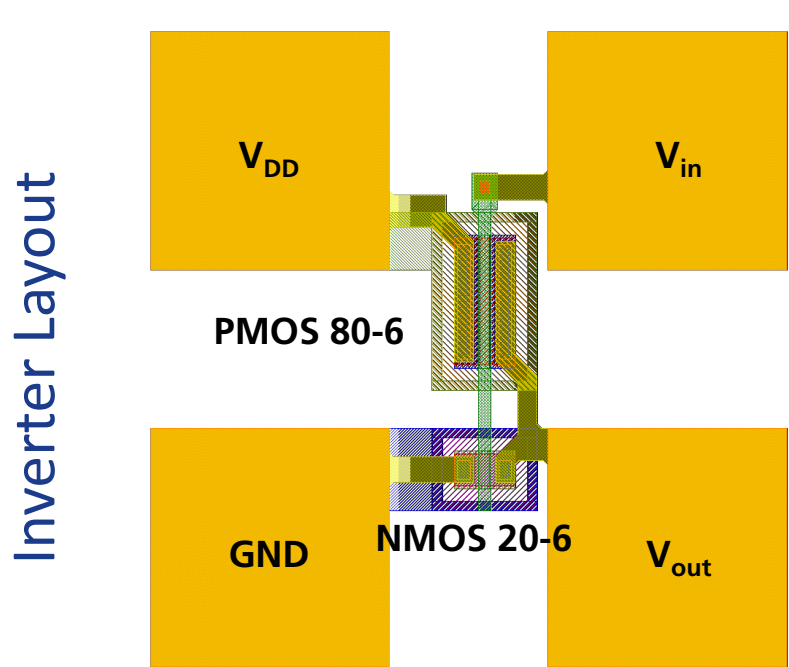
- Technology overview

Top View of Circuit Blocks

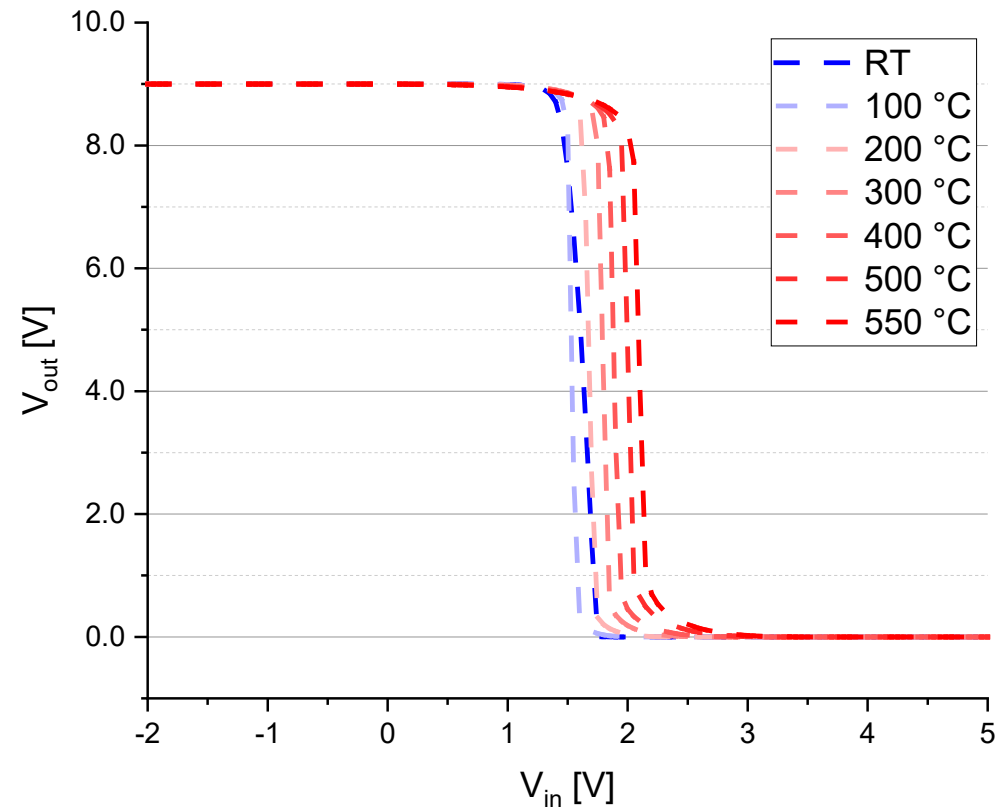


Circuit Cross-Cuts

- CMOS inverters up to 550 °C



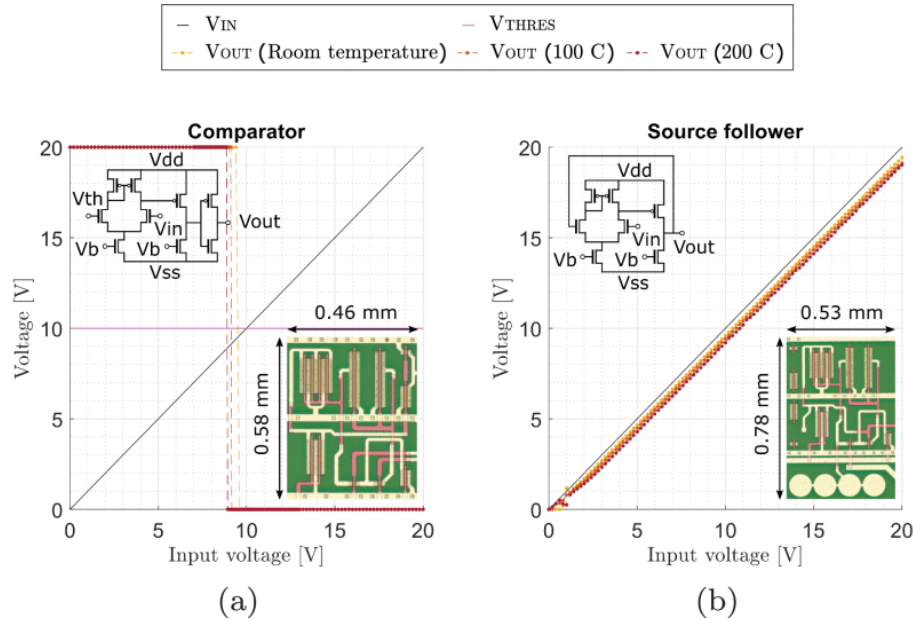
Temperature Dependence
of Transfer Characteristics



Development of System Building Blocks

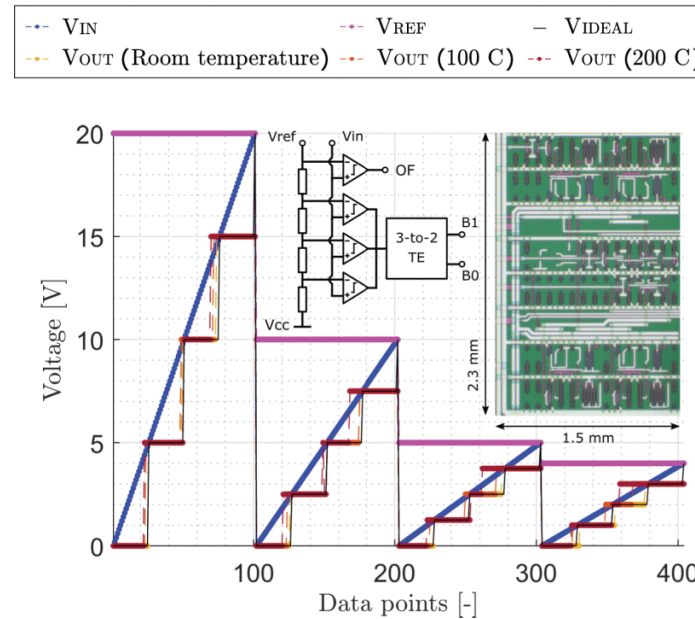
in cooperation with Delft University of Technology

Comparator & source follower

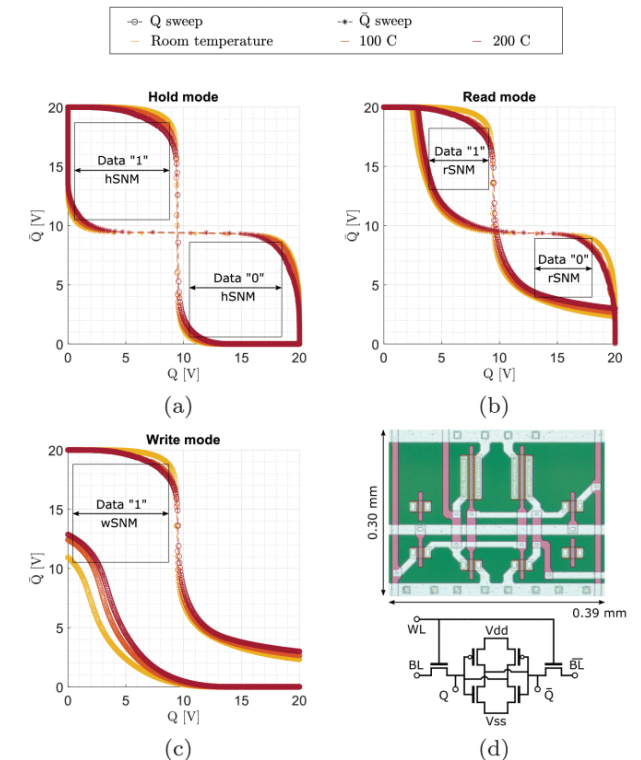


Integrated Digital and Analog Circuit Blocks in a Scalable Silicon Carbide CMOS Technology
 Romijn et al. *IEEE Transactions on Electron Devices*, 2022

2-bit ADC



SRAM cells



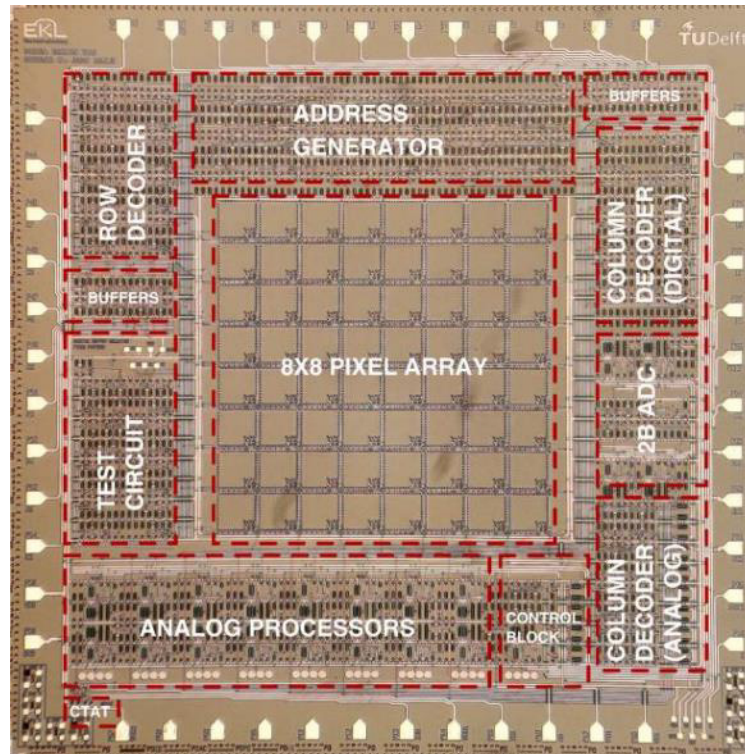
- Smart System Integration on SiC

8x8 UV pixel array with integrated read-out electronics

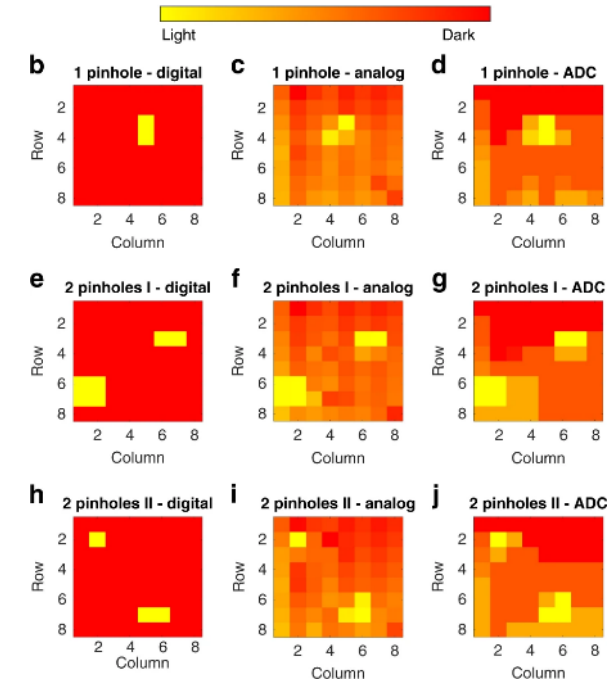
in cooperation with



System response



Integrated 64 pixel UV image sensor and readout in a silicon carbide CMOS technology
Romijn et al. *Microsystems & Nanoengineering*, 2022

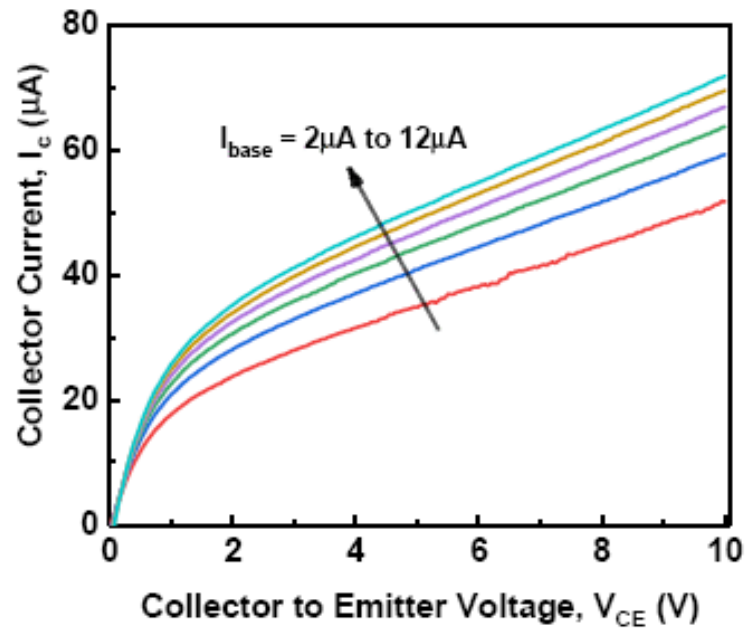


- SiC Smart Power Integration

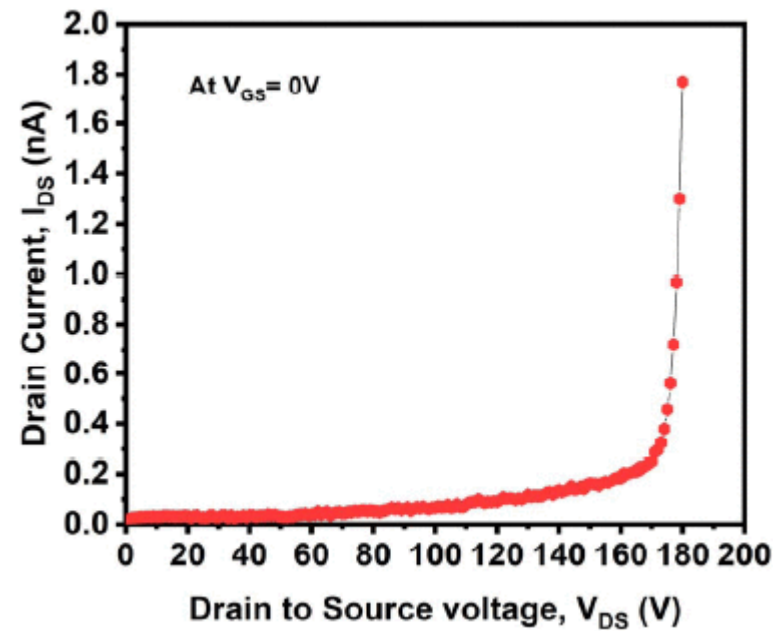
in cooperation with



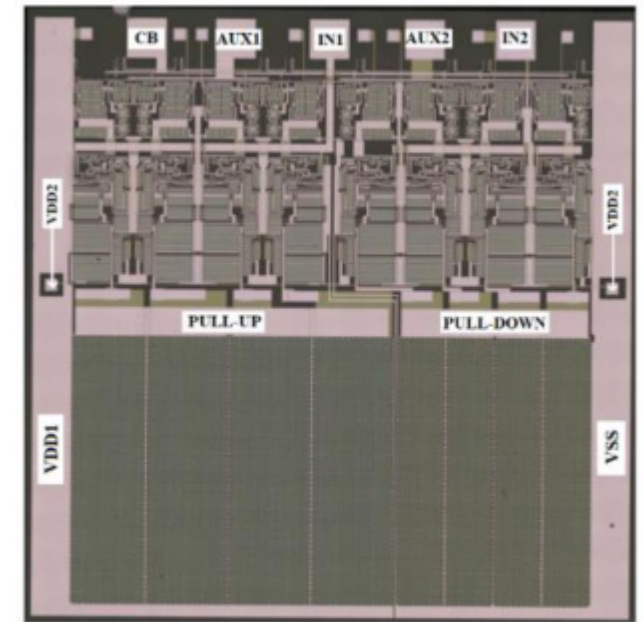
Bipolar Junction Transistor
Output Characteristics



LDMOS ($W = 30 \mu\text{m}$, $L = 5 \mu\text{m}$)
Breakdown at RT

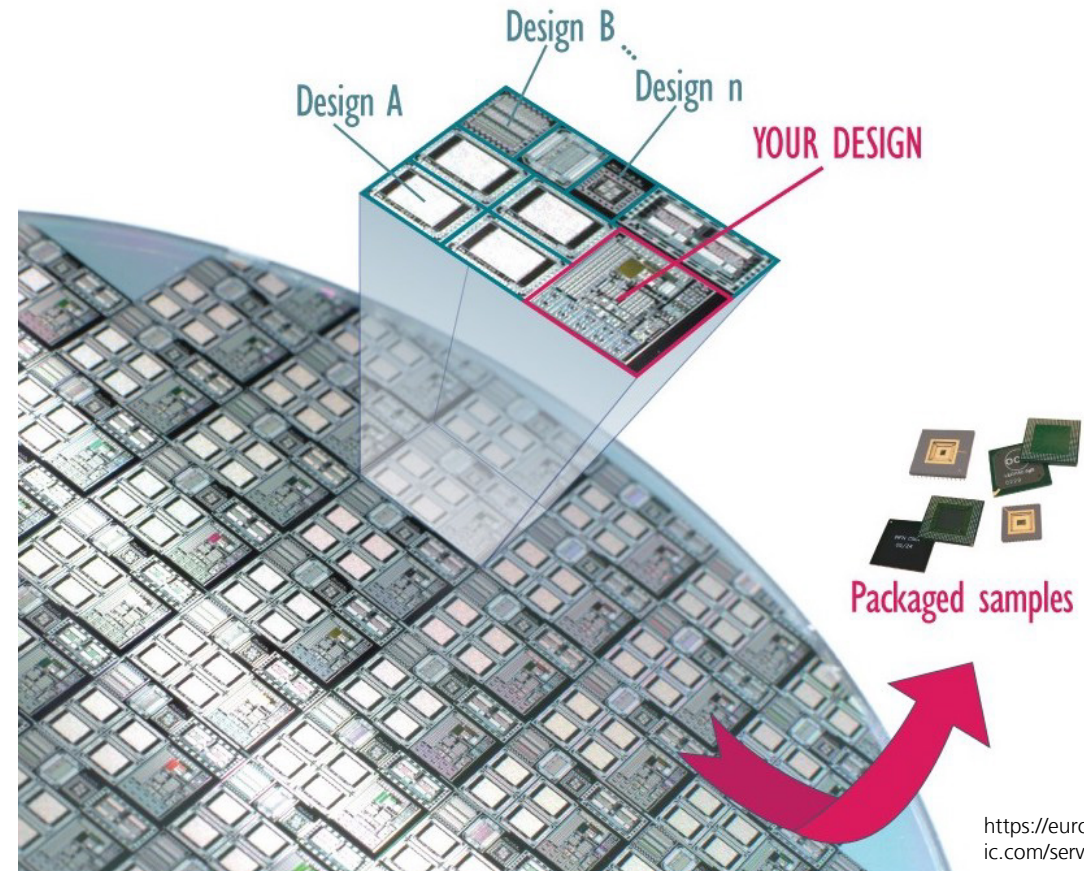


Multi-Level 5 x 5 mm²
Gate Driver



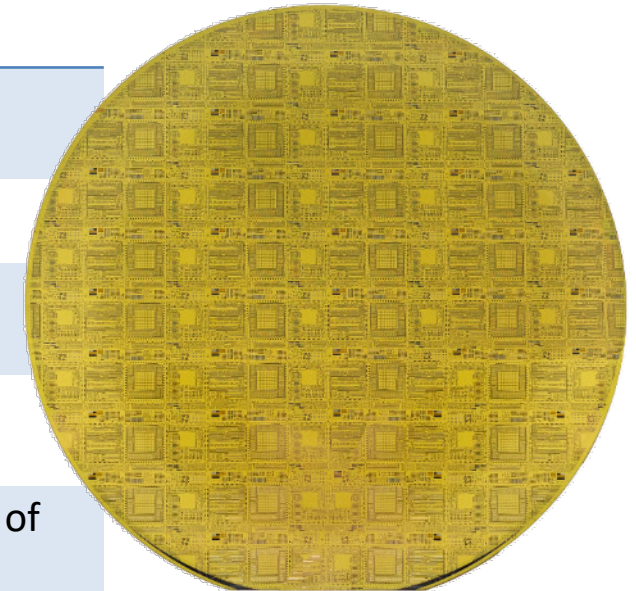
- Access

- Customer designs are combined in a mask set and processed jointly
- Process cost are distributed according to areal share
- Each customer gets delivered single chips of their layout
- Allows for participation in CMOS process flow starting from approx. 5% of total processing cost



- Process Options

Module	Description
RESURF I ²	Implantation Layer for Integration of CMOS with High-Voltage Power Switches towards Smart Power Systems
UV I ²	Implantation Module for monolithically integrated UV-Diodes
CUSTOM I ²	Customized Implantations for Application-Specific Devices
AL METAL	Low-Temperature Metallisation with Low Electrical Resistivity
GRIND	Wafer Backthinning for Advanced Applications and Optional Integration of Vertical Devices
SINTER	Backside Metallization for Silver Sintered High-Temperature Die Attach



Summary

- Unique SiC processing line for power, mixed-signal CMOS and sensors
- Research and development into advanced power devices
- Electronics for harsh environment
 - Available via EURO PRACTICE
- Quantum sensing and computing based on Si vacancies in SiC



THANK YOU



This project has received funding from the European Union's Horizon Europe research and innovation programme under GA N° 101092562

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